

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re Application of:

Kei YOSHIKAWA et al.

Group Art Unit: 2624

Application No.: 09/662,219

Examiner: Samir Anwar AHMED

Filed: September 14, 2000

Confirmation No.: 9438

For:

PATTERN CORRECTING METHOD OF

MASK FOR MANUFACTURING A SEMICONDUCTOR DEVICE AND RECORDING MEDIUM HAVING RECORDED ITS PATTERN **CORRECTING METHOD**

Mail Stop Amendment

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

<u>AMENDMENT</u>

In reply to the Office Action mailed April 6, 2007, the period for response having been extended to September 6, 2007, by a request for extension of two months and fee payment filed concurrently herewith, please amend the above-identified application as follows:

Amendments to the Specification are included in this paper.

Amendments to the Claims are reflected in the listing of claims in this paper.

Remarks/Arguments follow the amendment sections of this paper.

TO ENTER